

TITLE:

CLEANING CHEMICAL LIQUID SUPPLY DEVICE AND CLEANING CHEMICAL LIQUID
SUPPLY METHOD

5

ABSTRACT

A cleaning chemical liquid supply device includes: first and second mixers respectively
mixing first chemical liquid with dilution water and respectively supplying to first and second
10 nozzles respectively supplying the first chemical liquid adjusted to desired flow rates and
concentrations to a first position and a second, different position of the substrate in the cleaning
device; a first dilution water control box controlling flow rates of the dilution water supplied to
the first and second mixers; third and fourth mixers respectively mixing second, different
chemical liquid with the dilution water and respectively supplying to third and fourth nozzles for
15 respectively supplying the second chemical liquid adjusted to desired flow rates and
concentrations to a third position and a fourth, different position of the substrate in the cleaning
device; and a second dilution water control box controlling flow rates of the dilution water
supplied to the third and fourth mixers.

20 FIG. 2